# EXAFS analysis of local structures around Tb ions implanted in SiO<sub>2</sub> by detecting x-ray-excited visible luminescence

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## **Introduction**

Rare-earth doped semiconductors have been attracting much interest for possible applications in light-emitting devices and for their unique optical properties. Intra-4f-shell luminescence of rare-earth ions doped in semiconductor is sharp and temperature-stable. For example, it is reported that Tb ions implanted in SiO<sub>2</sub>:Tb thin film on Si showed strong visible luminescence at room temperature [1]. However, the luminescence intensity in the SiO<sub>2</sub>:Tb thin film has been found to depend strongly on growth conditions. In this work, local structures around optically active Tb ions implanted in SiO<sub>2</sub> on Si, which exhibited strong green luminescence (540 nm) at room temperature, were investigated site-selectively x-ray-excited by using visible luminescence EXAFS analysis.

#### **Experimental**

SiO<sub>2</sub> films of 200 nm thickness, which were formed by dry thermal oxidation, were grown on p-Si(001). Tb ion was introduced into the oxide layer by ion implantation. The implantation was performed at 300keV. Dose density of Tb implanted in SiO<sub>2</sub> was  $1 \times 10^{15}$  Tb ions/cm<sup>2</sup>. Annealing of the SiO<sub>2</sub>:Tb film was performed in vacuum (~10<sup>-5</sup> Torr) at 900 °C for 30min. The EXAFS measurements were performed at the beam line BL9A at KEK-PF. X-ray-excited visible luminescence was detected by CCD detector or photomultiplier.

### **Results and discussion**

Figure 1 shows the photoluminescence spectra for  $SiO_2$ :Tb excited by synchrotron radiation (SR) and Ar<sup>+</sup> laser. By X-rat-excited visible luminescence due to Tb intra-4f transition was observed clearly. Figure 2 shows visible luminescence intensity excited by SR and fluorescence x-ray intensity. By detecting visible luminescence due to Tb intra-4*f* transition, oscillatory spectrum was clearly observed, suggesting that there is a possibility of EXAFS analysis for SiO<sub>2</sub>:Tb by detecting x-ray-excited visible luminescence.

#### **References**

[1] H. Amekura et al., J. Appl. Phys. 84 (1998) 3867.

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Fig.1 Photoluminescence spectra for  $SiO_2$ :Tb excited by (a) synchrotron radiation (SR) and (b)  $Ar^+$  laser. Photoluminescence was detected by CCD.



Fig. 2: Visible luminescence intensity excited by SR and fluorescence x-ray intensity.